

## Supporting Information

### **Solution-Processed Sensing Textiles with Adjustable Sensitivity and Linear Detection Range Enabled by Twisting Structure**

*Zengyu Hui,<sup>†Δ</sup> Ruyi Chen,<sup>†Δ</sup> Jin Chang,<sup>†Δ</sup> Yujiao Gong,<sup>†</sup> Xianwang Zhang,<sup>§</sup> Hai Xu,<sup>†</sup> Yue Sun,<sup>†</sup> Yue Zhao,<sup>†</sup> Lumin Wang,<sup>†</sup> Ruicong Zhou,<sup>†</sup> Feng Ju,<sup>§</sup> Qiang Chen,<sup>‡</sup> Jinyuan Zhou,<sup>⊥</sup> Jianing An,<sup>¶</sup> Gengzhi Sun,<sup>\*,†‡</sup> and Wei Huang<sup>†‡</sup>*

<sup>†</sup>Institute of Advanced Materials (IAM), Nanjing Tech University (NanjingTech),  
Nanjing 211816, P. R. China

<sup>‡</sup>Institute of Flexible Electronics (IFE), Northwestern Polytechnical University (NPU),  
Xi'an 710072, P. R. China

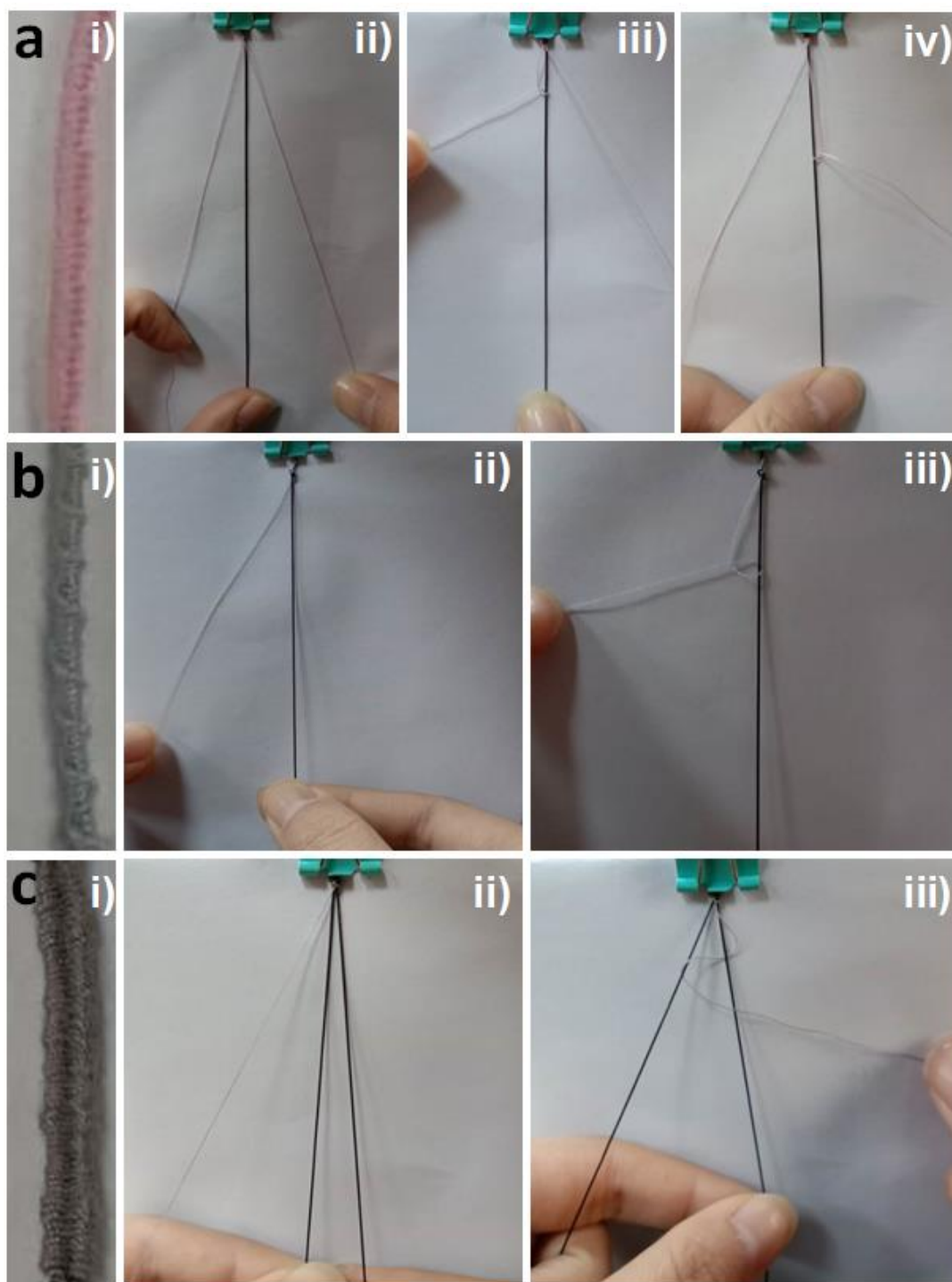
<sup>§</sup>School of Mechanical and Electrical Engineering, Nanjing University of Aeronautics  
and Astronautics, Nanjing 210016, P. R. China

<sup>‡</sup>School of Materials Science and Engineering, Henan Polytechnic University, Jiaozuo  
454003, P. R. China

<sup>⊥</sup>School of Physical Science and Technology, Lanzhou University, Lanzhou 730000,  
P. R. China

<sup>¶</sup>School of Mechanical and Aerospace Engineering, Nanyang Technological  
University, 50 Nanyang Avenue, 639798, Singapore

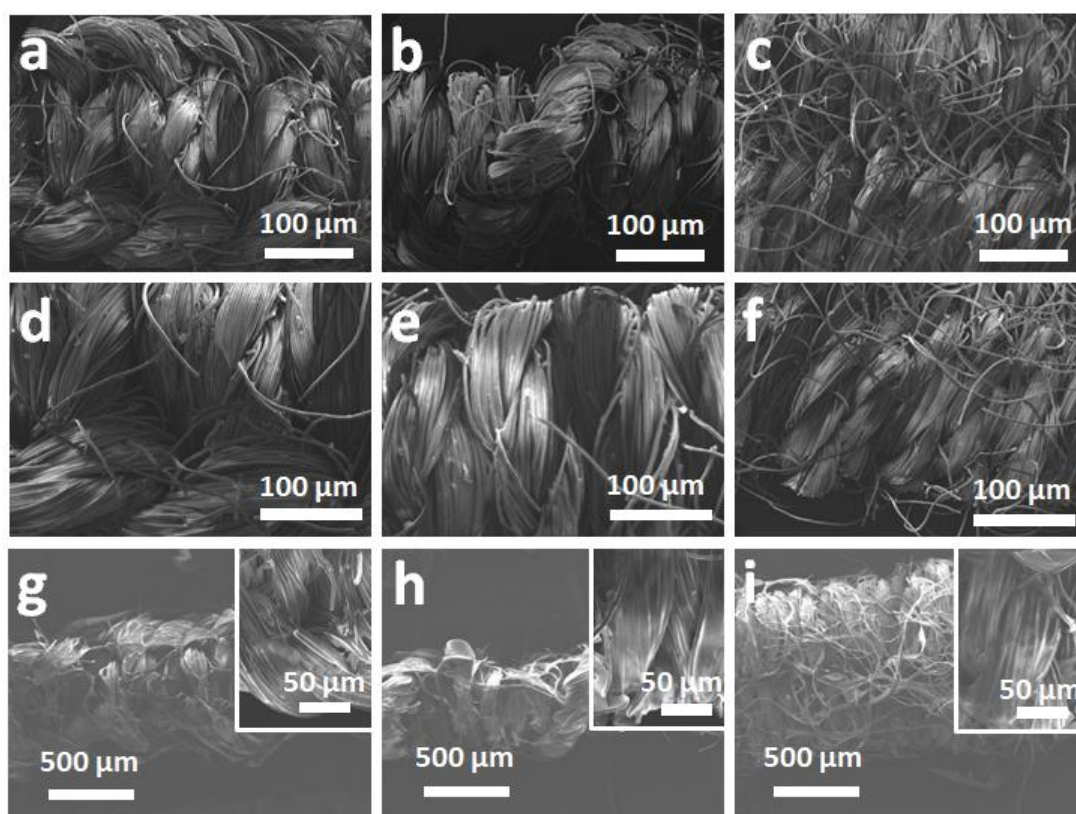
<sup>\*</sup>Corresponding author. E-mail address: iamgzsun@njtech.edu.cn



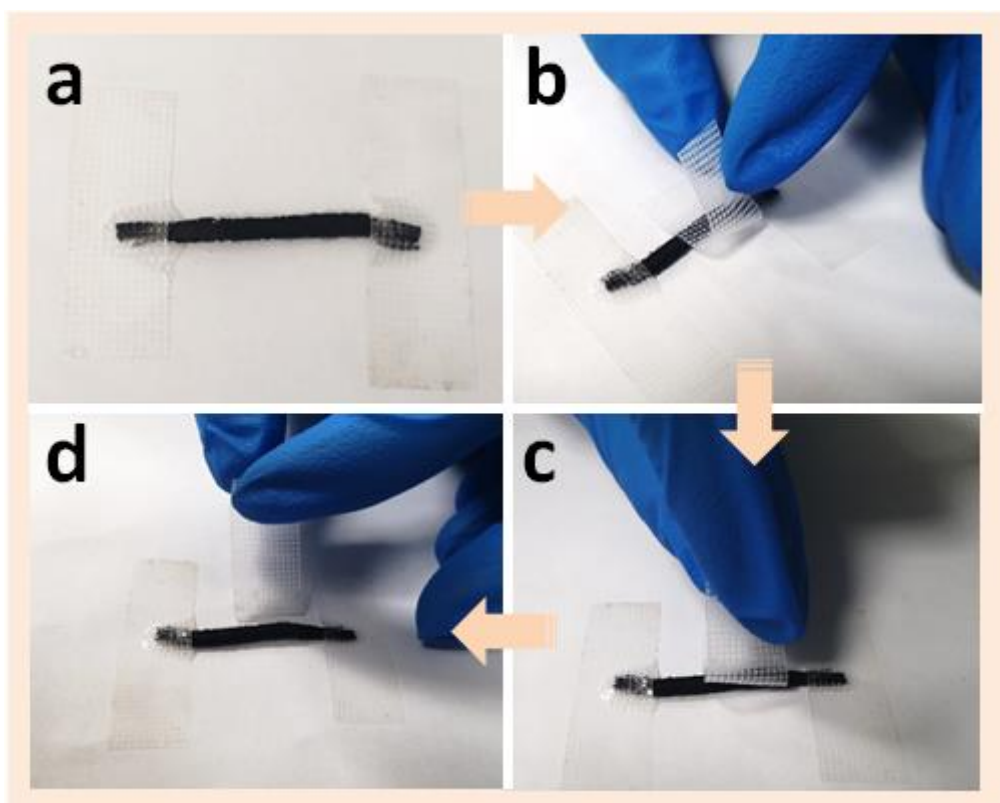
**Figure S1.** Twisting procedures for three predesigned models: a) Model 1, b) Model 2, and c) Model 3.



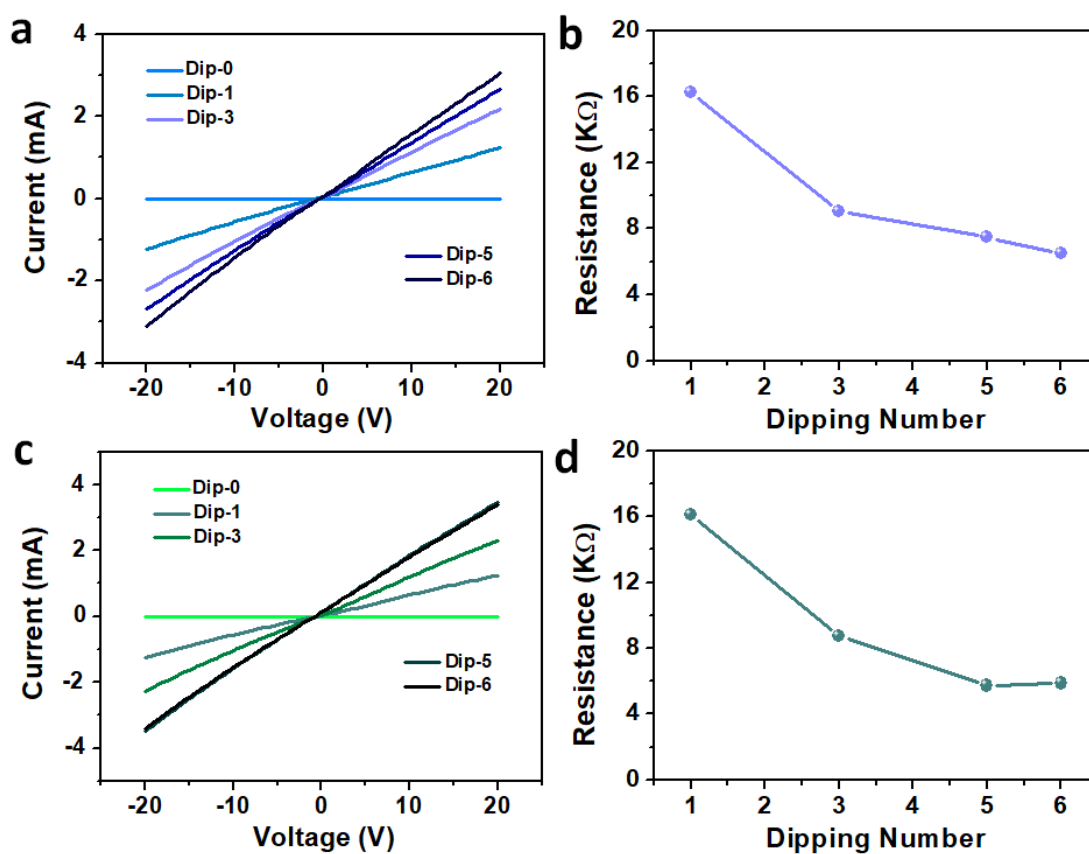
**Figure S2.** Photograph of as-prepared PPy without PVA.



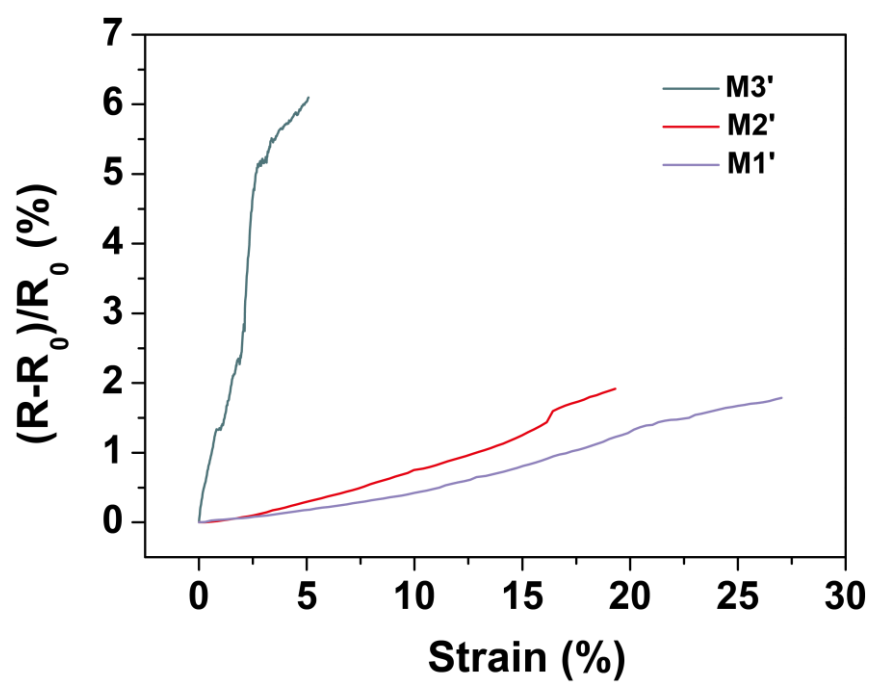
**Figure S3.** SEM images of the textiles before and after dip-coating: a-c) SEM images of as-twisted textiles of M1, M2, M3, respectively; d-f) high-magnification SEM images of original textiles of M1, M2, M3; g-i) SEM images of M1, M2, M3 dip-coated by conductive ink. Insets correspond to high-magnification SEM images of PPT-M1, PPT-M2 and PPT-M3.



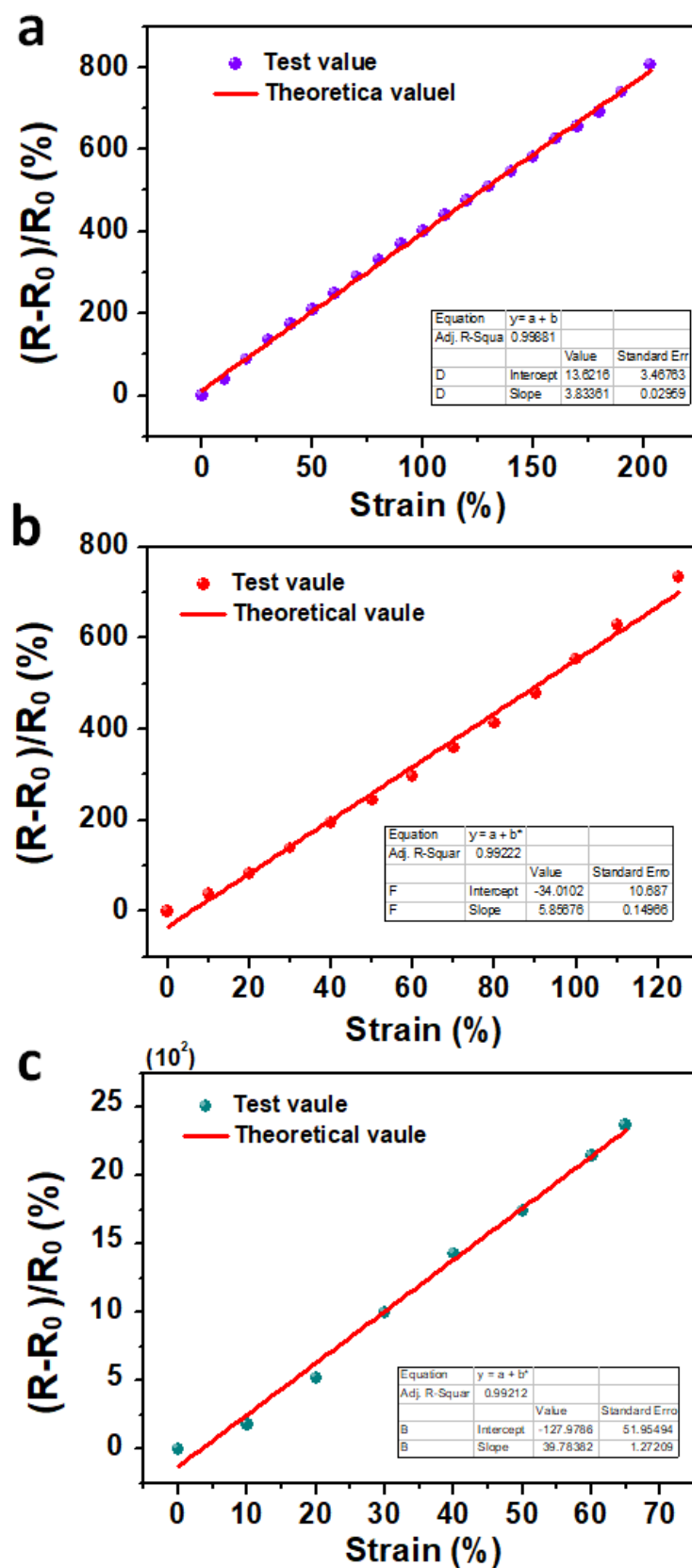
**Figure S4.** a-d) Demonstration of good adhesion between conductive sheath and core yarn by attaching onto and peeling off a adhesive tape.



**Figure S5.** a) Current-voltage curve of PPTS-M1 with varying dip-coating times (one to six). b) Resistance of PPTS-M1 with varying dip-coating times. c) Current-Voltage curve of PPTS-M2 with varying dip-coating times (one to six). d) Resistance of PPTS-M2 with varying dip-coating times.

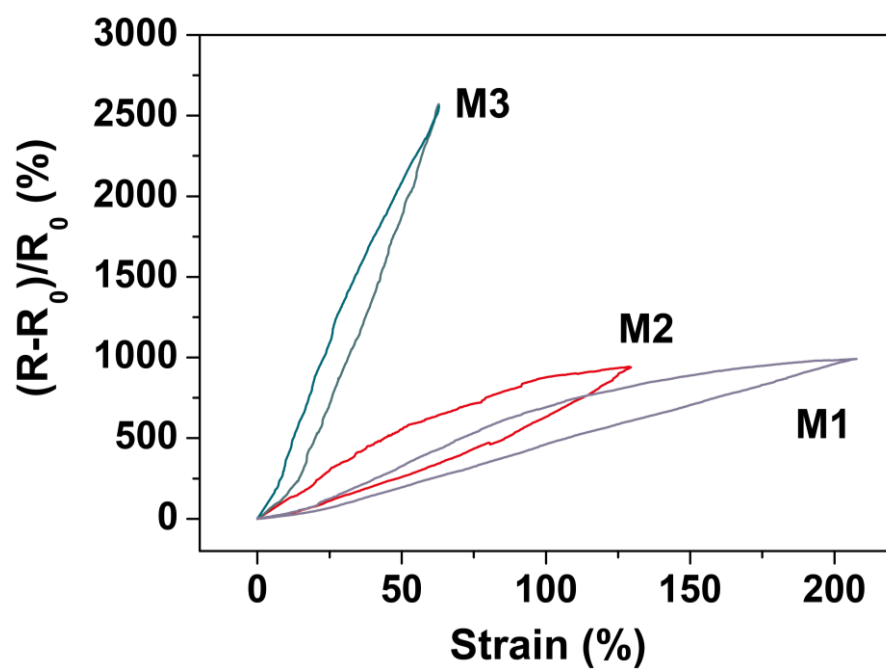


**Figure S6.** Resistance variation of three models without central elastomer during tension.

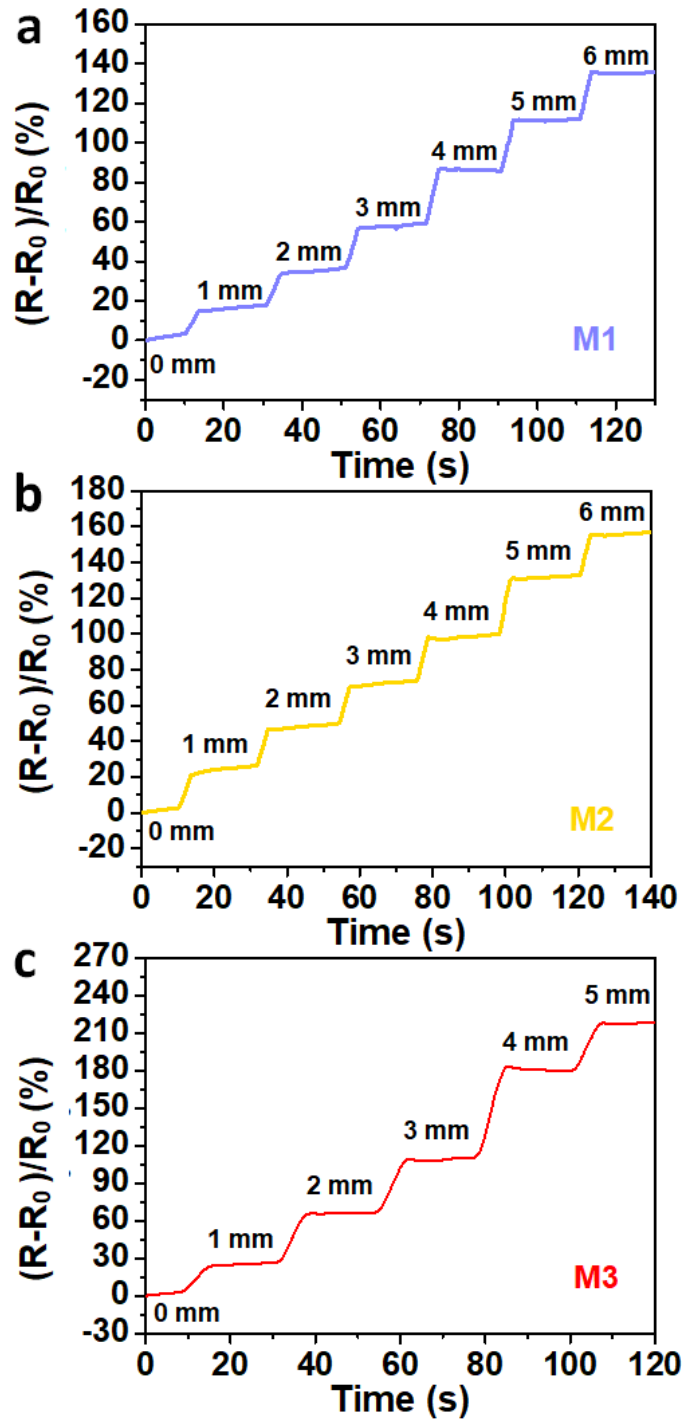


**Figure S7.** a-c) Linearity fit of resistance change for PPTS-M1, PPTS-M2 and PPTS-M3 during tension, respectively.

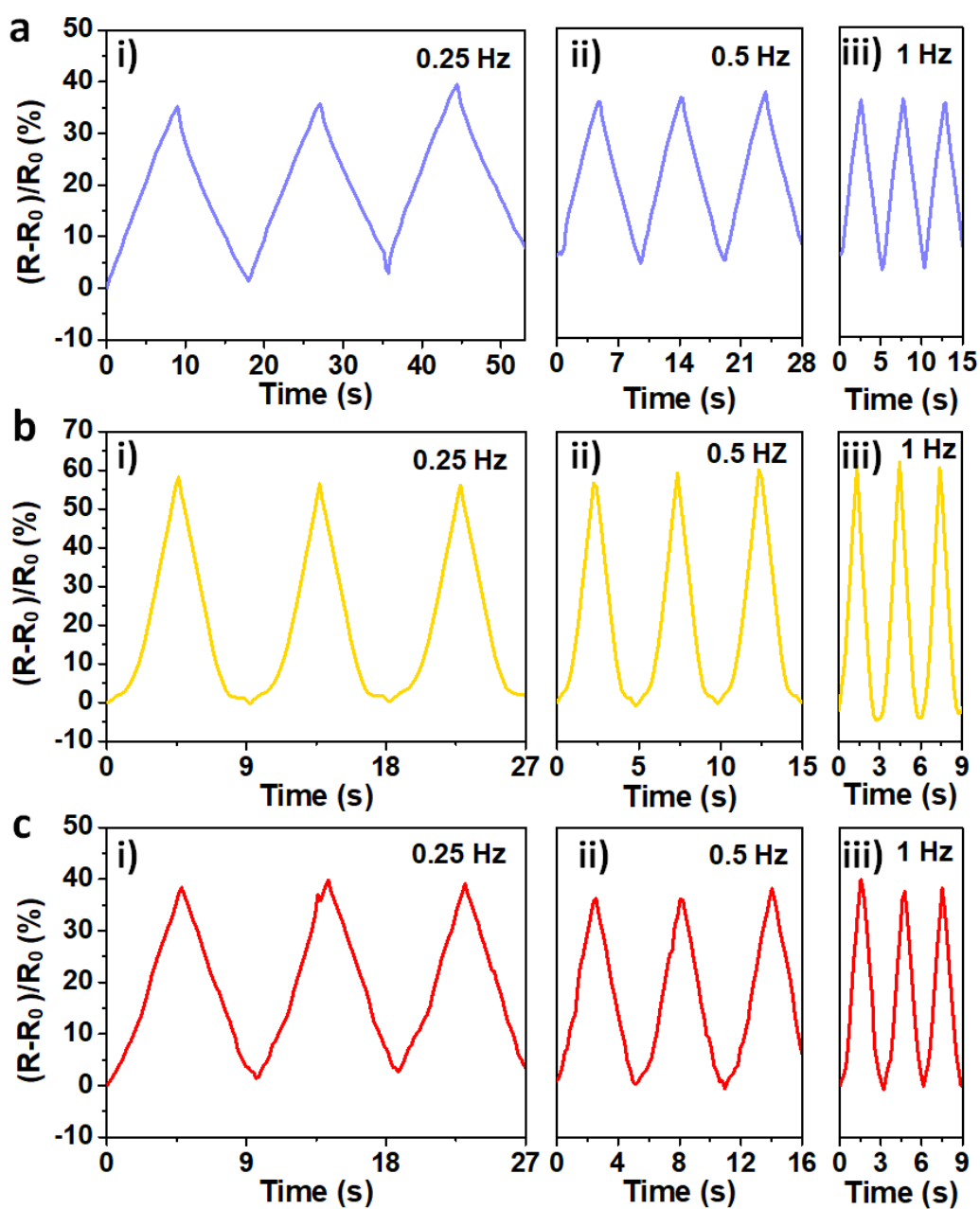




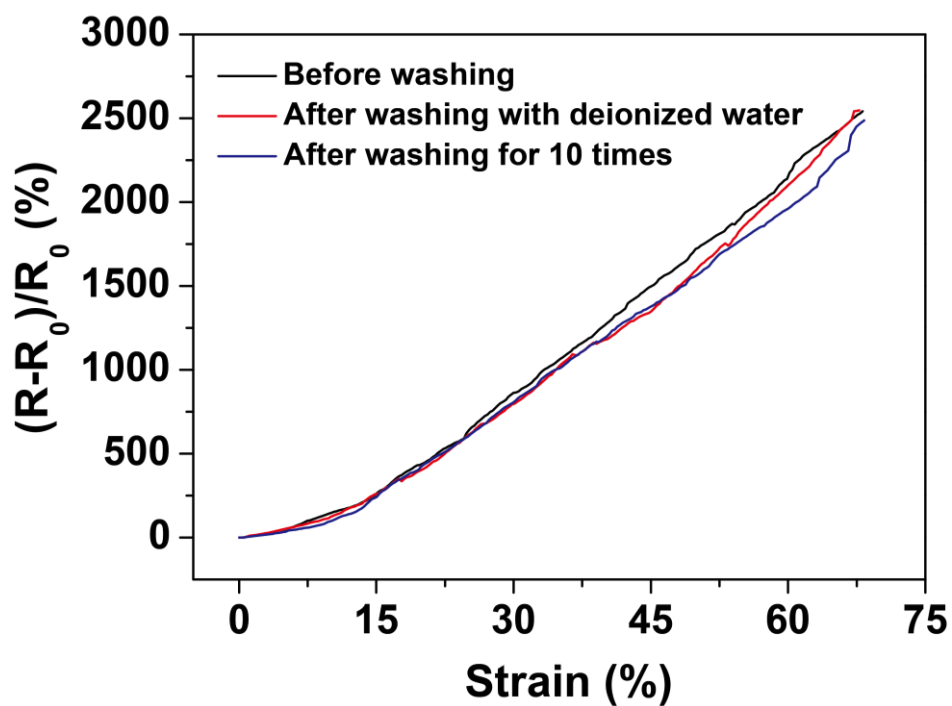
**Figure S8.** The hysteresis behavior of PPTS-M1, PPTS-M2 and PPTS-M3.



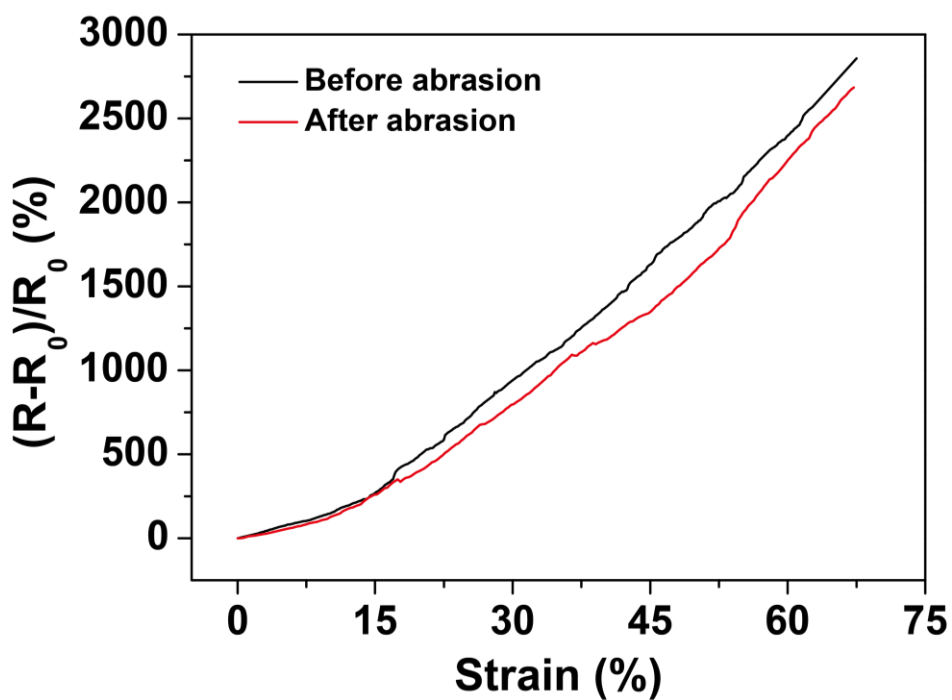
**Figure S9.** a-c) Relative resistance change of PPTS-M1, PPTS-M2 and PPTS-M3 at different strains.



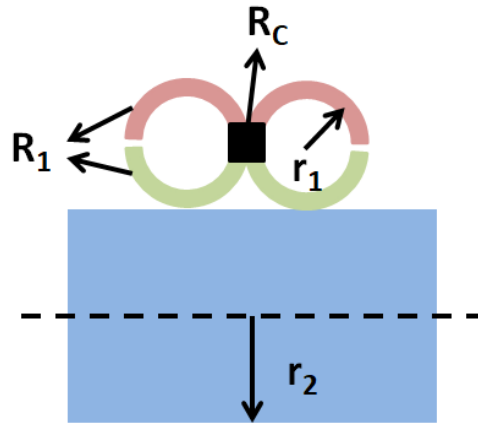
**Figure S10.** a-c) Relative resistance variation under cyclic stretching/releasing at frequencies of 0.25, 0.5, and 1 Hz for PPTS-M1, PPTS-M2 and PPTS-M3, respectively.



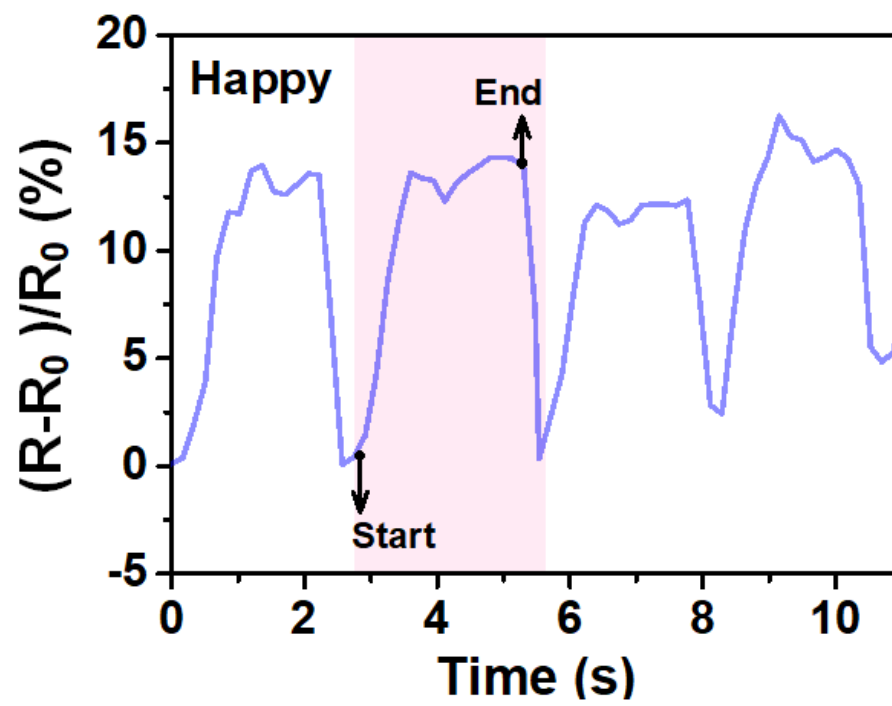
**Figure S11.** The performance of PPTS-3 before and after washing.



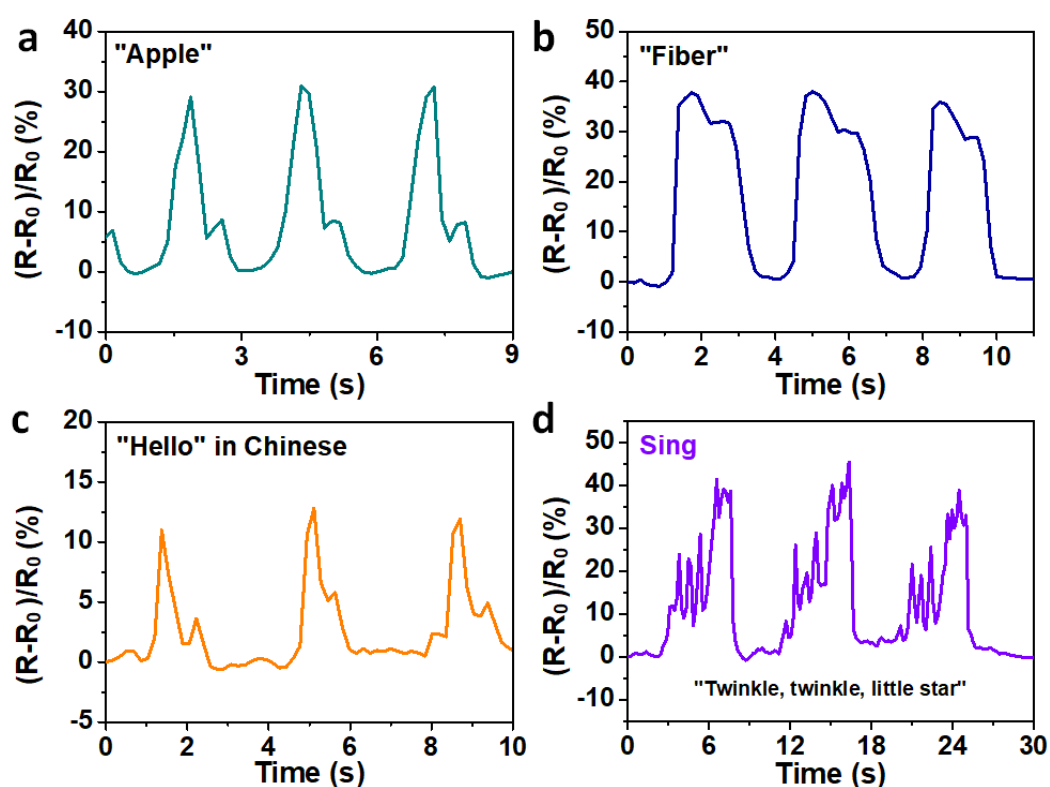
**Figure S12.** The performance of PPTS-3 before and after abrasion.



**Figure S13.** The longitudinal section of the structure.



**Figure S14.** Application of PPTS-M3 for detecting the motion of mouth when the person is happy.



**Figure S15.** a-b) Applications of PPTS-M3 for vocal cords vibration when speaking “Apple” and “Fiber” in English, respectively. c) Signals when speaking “Hello” in Chinese. d) Signals when singing a song.

**Table S1.** Performance comparison between our sensors and those reported in literatures.

| Strain sensors   | Maximal workable strain range | Average gauge factor   | Relationship in resistance under strain | Sign of gradient | Ref. |
|--|-------------------------------|--|---|------------------|------|
| PPy-coated fabrics (Lycra)                                   | 60 %                          | ~-3.5 (at 20 % strain)<br>~-0.7 (at 60 % strain)                             | None-linear                             | Negative         | 1    |
| Graphene based on yarns (NCRY )                              | 150%                          | 1.4  | Linear                                  | Positive         | 2    |
| Graphene based fiber with “compression spring” Structure     | 100%                          | 10 (1% Strain)<br>3.7 (50% Strain)   | None-linear                             | Positive         | 3    |
| Graphene textile without polymer encapsulation               | 8%                            | -26  | None-linear                             | Negative         | 4    |
| Carbonized plain-weave silk fabric with Ecoflex encapsulated | 500%                          | 5.8 (under 1% strain)<br>9.6 (within 250% strain)<br>37.5 (250%-500% strain) | 3 linear regions                        | Positive         | 5    |
| Graphene–Nanocellulose Nanopaper                             | 100%                          | 1.6 (10% strain)<br>7.1 (100% strain)  | Exponential                             | Positive         | 6    |
| Carbon nanotube film on PDMS                                 | 280%                          | 0.82 (40% strain)<br>0.06 (60-200% strain)                                   | 2 linear regions                        | Positive         | 7    |
| Carbon black thermal plastic elastomer composite             | 80%                           | 20   | None-linear                             | Positive         | 8    |
| Silver nanoparticles   | 20%                           | 2.05   | Linear                                  | Positive         | 9    |
| Laser-scribed graphene                                       | 10%                           | 9.49   | Linear                                  | Positive         | 10   |
| PPTSs  | 200%                          | 3.8  | Linear                                  | Positive         | M1   |
|  | 125%                          | 5.9  |   |                  | M2   |
|  | 65%                           | 38.9   |   |                  | M3   |



## References

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